

Attorney's Docket 071469-0273243  
Client Reference: PC0033AREG



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

RECEIVED  
DEC 09 2003  
TC 1700

In re PATENT APPLICATION of:  
WAYNE L JOHNSON ET AL.

Confirmation Number: 8536

Application No.: 10/076,099

Group Art Unit: 1753

Filed: February 15, 2002

Examiner: Rodney G. McDonald

For: PULSED PLASMA PROCESSING METHOD AND APPARATUS

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

AMENDMENT/RESPONSE TRANSMITTAL

Transmitted herewith is an amendment/response for this application.

FEES

The fee for claims and extension of time (37 C.F.R. 1.16 and 1.17) has been calculated as shown below:

	CLAIMS										
	REMAINING	HIGHEST NO.									
	AFTER	PREVIOUSLY									
	AMENDMENT	PAID FOR									
TOTAL	27	-	26	=	1	x	\$	18.00	=	\$	18.00
INDEP.	3	-	3	=	0	x	\$	86.00	=	\$	0.00
FIRST PRESENTATION OF MULTIPLE DEP. CLAIM				+	\$	290.00	=	\$	0.00		
TOTAL ADDITIONAL CLAIM FEE											\$ 18.00
GRAND TOTAL											\$ 18.00

FEE PAYMENT

Authorization is hereby made to charge the amount of \$18.00 to Deposit Account No. 033975. Charge any additional fees required by this paper or credit any overpayment in the manner authorized above. A duplicate of this paper is attached.

Date: 12/15/03

  
DALE S. LAZAR  
Reg. No. 28872

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Title: PULSED PLASMA PROCESSING METHOD AND APPARATUS

December 5, 2003

\* \* \* \* \*

AMENDMENT

Hon. Commissioner of Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action dated September 5, 2003, please amend this application as follows:

IN THE CLAIMS:

1. (Original) A method for performing a plasma-assisted treatment on a substrate in a reactor chamber, comprising:
  - introducing at least one process gas into the reactor chamber;
  - creating a plasma within the reactor chamber by establishing an RF electromagnetic field within the chamber and allowing the field to interact with the process gas; and
  - causing the electromagnetic field to have an energy level which varies cyclically between at least two values each sufficient to maintain the plasma, such that each energy level value is associated with performance of a respectively different treatment process on the substrate.